

Silicon isotope engineering for the development of better classical and quantum computers

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Contents

- 1. Silicon semiconductor engineering**
- 2. Better Si chips for classical computers**
 - Highly thermal conductive silicon
 - Probing thermal oxidation mechanism
 - Probing Si diffusion during heat processing
- 3. Superconductivity in $\text{Ba}_8\text{Si}_{46}$ clathrate**
- 4. All silicon quantum computers**
 ^{29}Si nuclear spins embedded in spin-free ^{28}Si matrix

Collaborators

Isotope engineering:

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Tomoko Shimizu (Keio University)

Katsumi Tanigaki (Osaka City University)

$\text{Ba}_8\text{Si}_{46}$ clathrate

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Yuzo Ohno (Tohoku University)

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1. Semiconductor Isotope Engineering

List of stable isotopes

^{28}Si 92.2%

^{69}Ga 60.1% $\rightarrow 3/2$

^{29}Si 4.7% $\rightarrow 1/2$

^{71}Ga 39.9% $\rightarrow 3/2$

^{30}Si 3.1% (nuclear spin)

(nuclear spin)

^{75}As 100% $\rightarrow 3/2$

^{70}Ge 20.5%

^{72}Ge 27.4%

^{73}Ge 7.8% $\rightarrow 9/2$
(nuclear spin)

^{74}Ge 36.5%

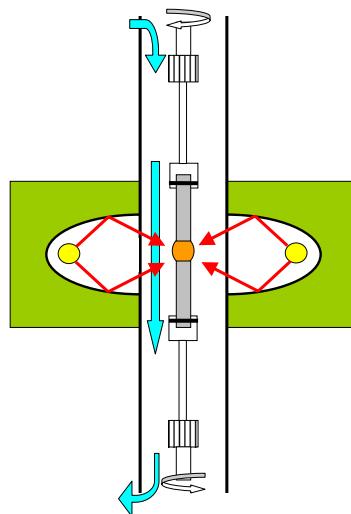
^{76}Ge 7.8%

Mass and nuclear spin
Control through manipulation
of stable isotopes

Si bulk crystal growth



Floating-zone Si grower



Isotopically controlled Si fabrication

Natural abundance

^{28}Si 92.2%

^{29}Si 4.7%

^{30}Si 3.1%

99.92% ^{28}Si single crystal

Neck

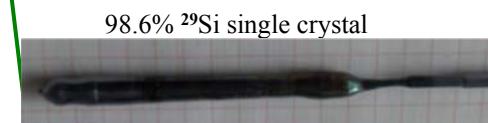
Single

50mm

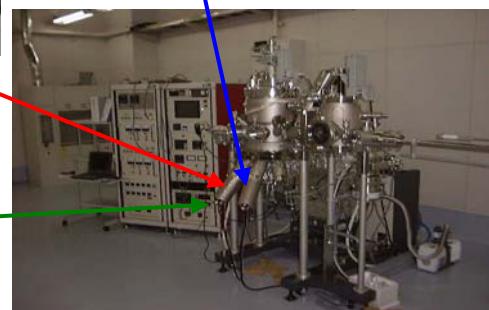


98.6% ^{29}Si single crystal

50mm



96% ^{30}Si single crystal



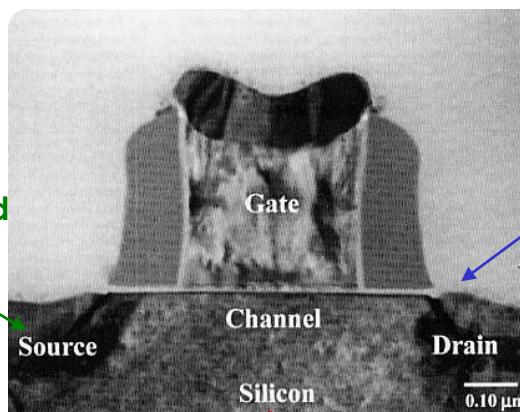
2. Better Si chips for classical computers

MOSFET

3. Impurity and Si diffusion

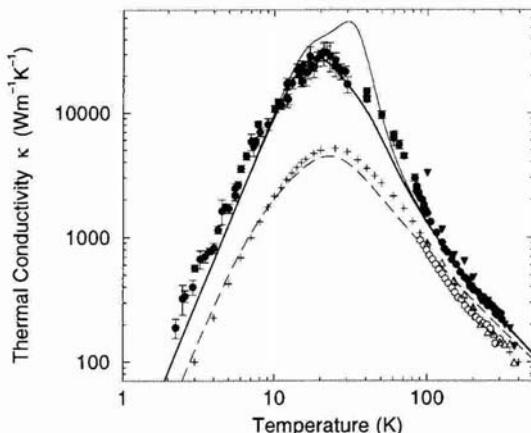
2. SiO_2 formation

1. Heat flow



Isotope effect on thermal conductivity of Si

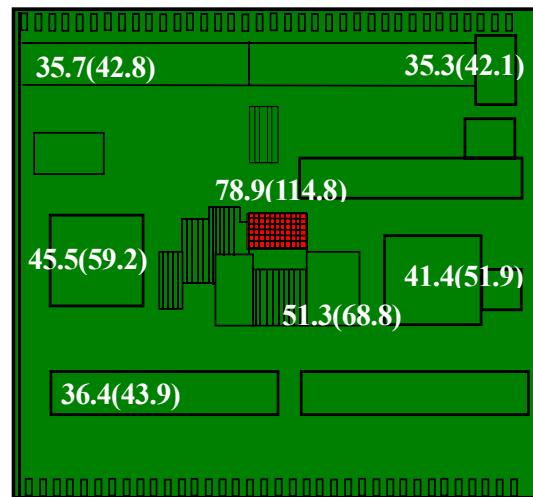
Thermal conductivity of 99.86% ^{28}Si



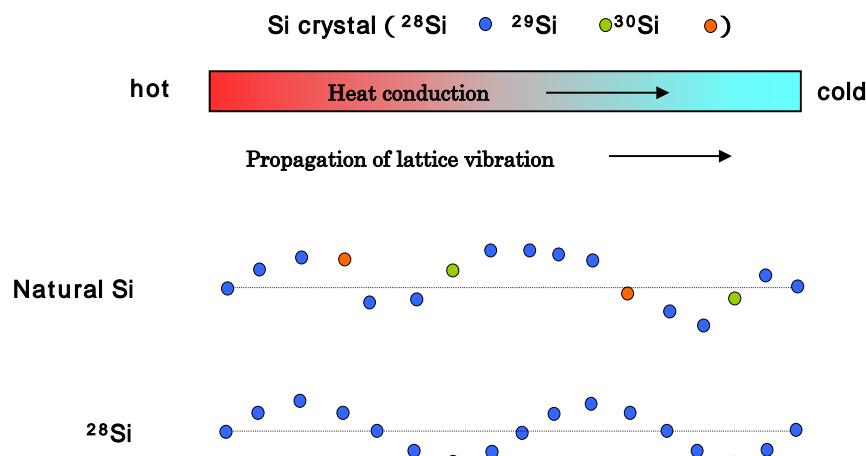
300K 60% increase
400K 40-50% increase
with respect to natural Si

Temperatures in a 1GHz microprocessor (simulation)

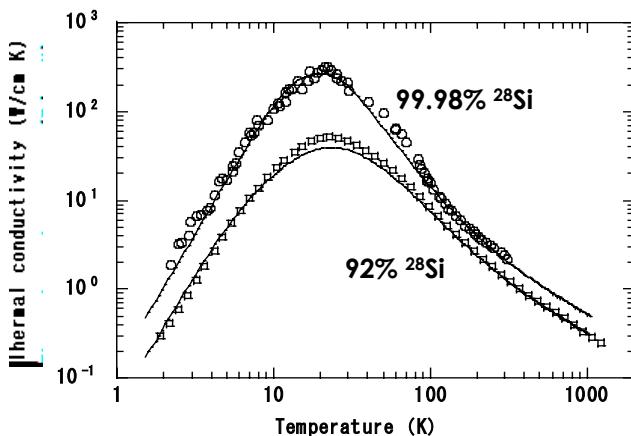
Temperatures in Celsius
for
an isotopically enriched
 ^{28}Si substrates and
a natural Si substrate
in parentheses



Thermal conductivity enhancement



Comparison with theory



1. Isotope scattering

$$g = \frac{\sum c_i M_i^2 - (\sum c_i M_i)^2}{(\sum c_i M_i)^2}$$

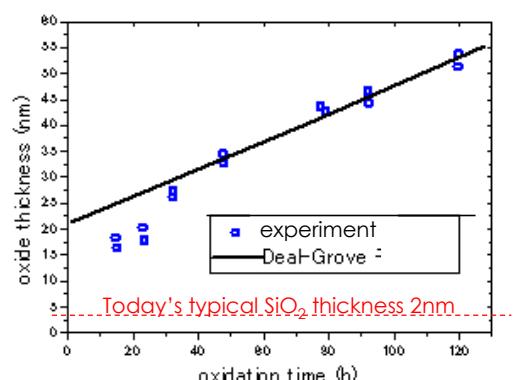
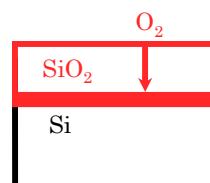
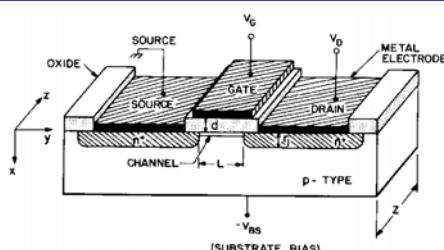
2. Boundary scattering

3. Normal process (phonon)

4. Umklapp process (phonon)

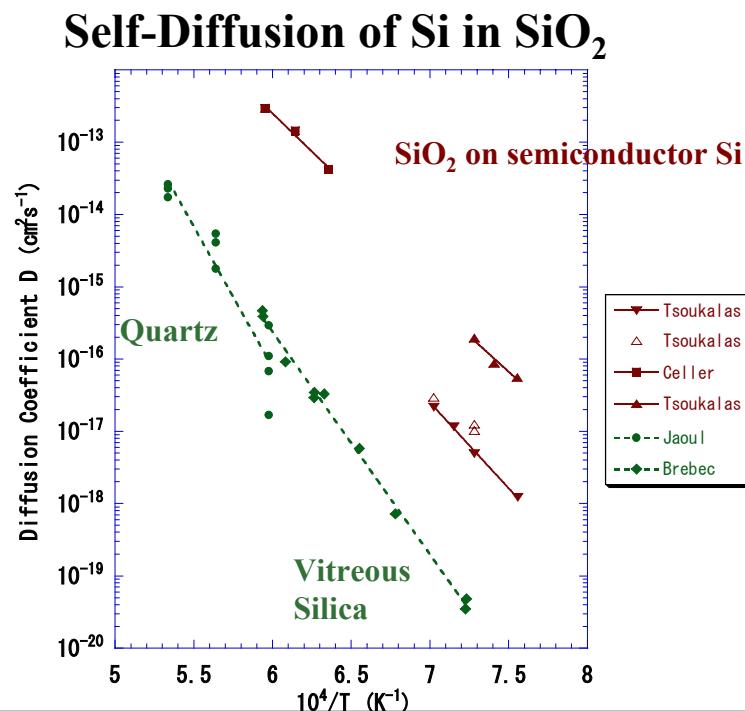
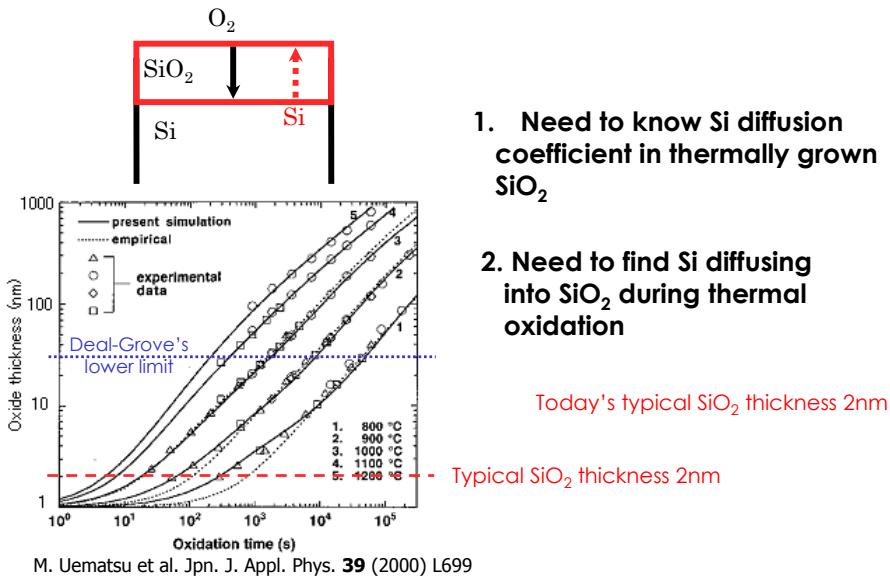
Fit based on M. G. Holland: Phys. Rev. **132** (1963) 2461

Thermal oxidation of Si

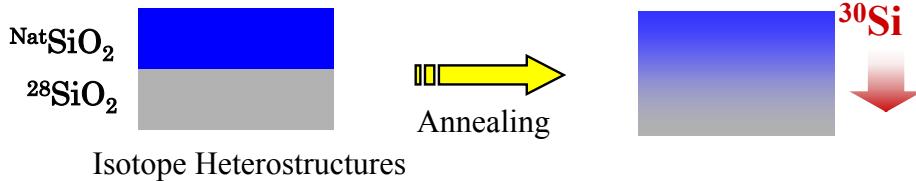


Deal and Grove's model
J.Appl.Phys.,**36**.3770(1965)

Does Si diffuse into SiO_2 ?



Diffusion studies with stable isotopes



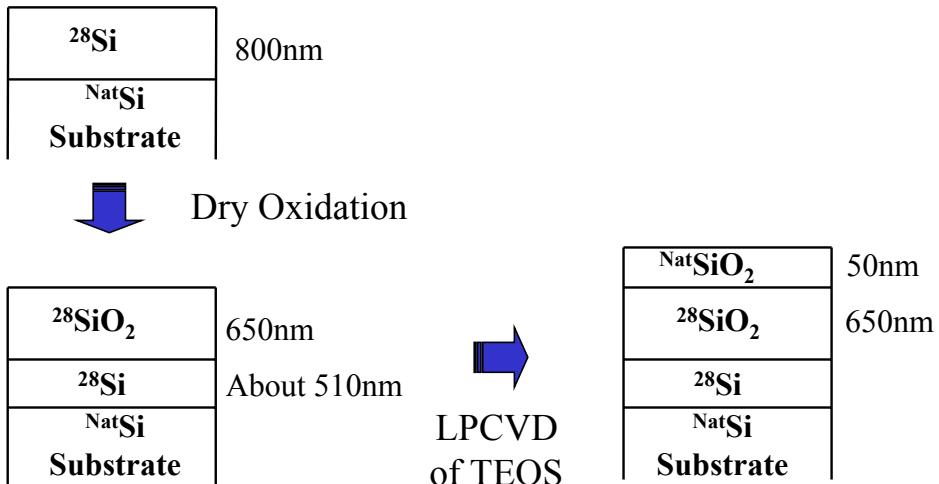
Diffusion of $^{30}\text{Si} \Rightarrow \text{SIMS Measurement}$

Isotope Composition of NatSiO_2 and $^{28}\text{SiO}_2$

Isotope	^{28}Si	^{29}Si	^{30}Si
NatSiO_2	92.2%	4.7%	3.1%
$^{28}\text{SiO}_2$	99.924%	0.073%	0.003%

Preparation of Samples

Using $^{28}\text{SiH}_4$



Annealing

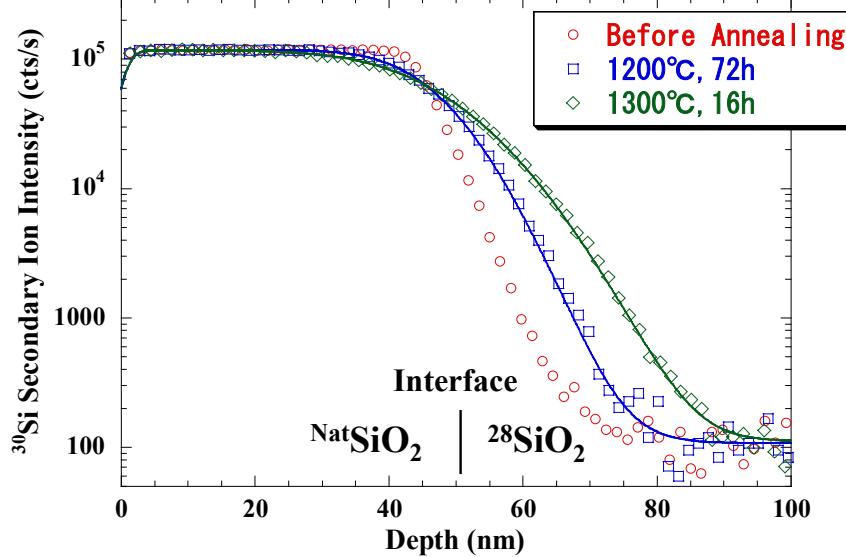
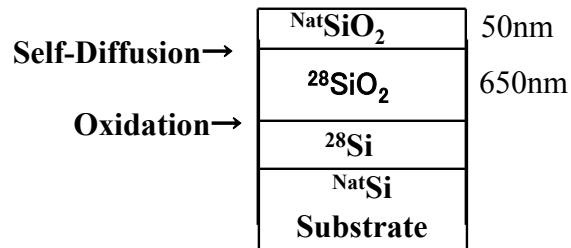
- 1150, 1200, 1250, 1300 °C

- Flowing Ar+1% O₂

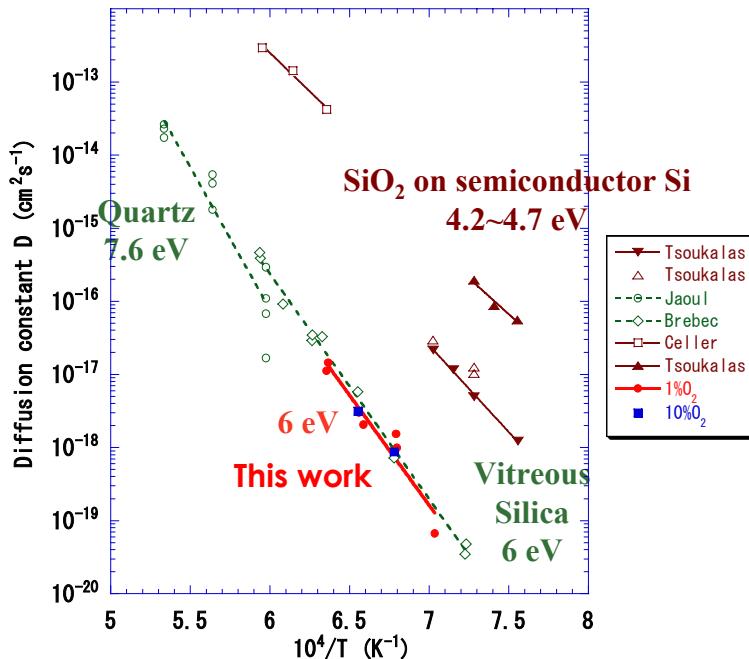
Oxygen prevents decomposition of SiO₂

Concentration of oxygen	Low	High
	↓	↓
	Decomposition	Oxidation

- Flowing Ar+20% O₂

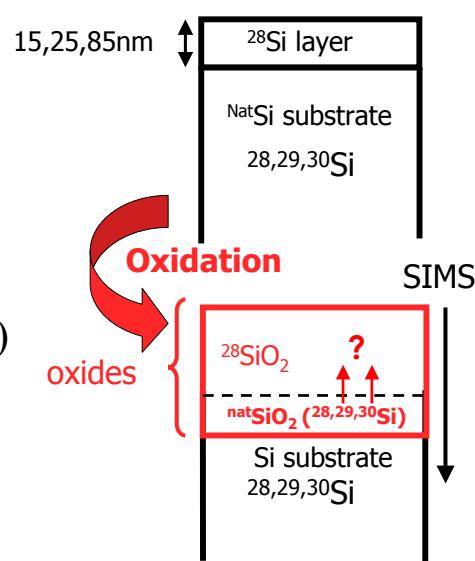


$$C(x) = C_{28} + \frac{C_{Nat} - C_{28}}{2} \left[erf\left(\frac{x+h}{2\sqrt{Dt}}\right) - erf\left(\frac{x-h}{2\sqrt{Dt}}\right) \right]$$

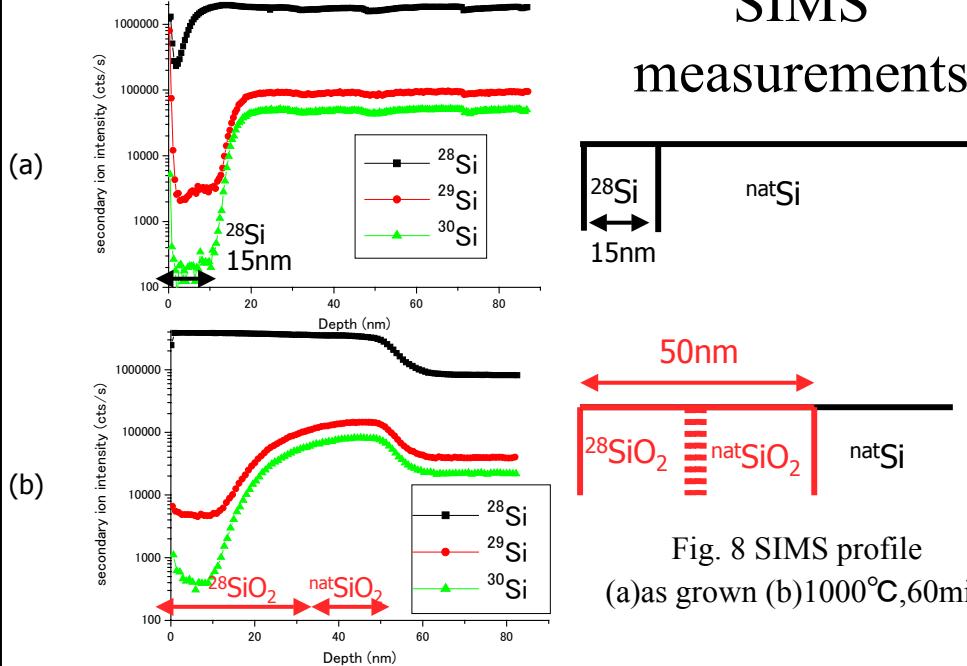


Direct observation of Si diffusion into SiO_2

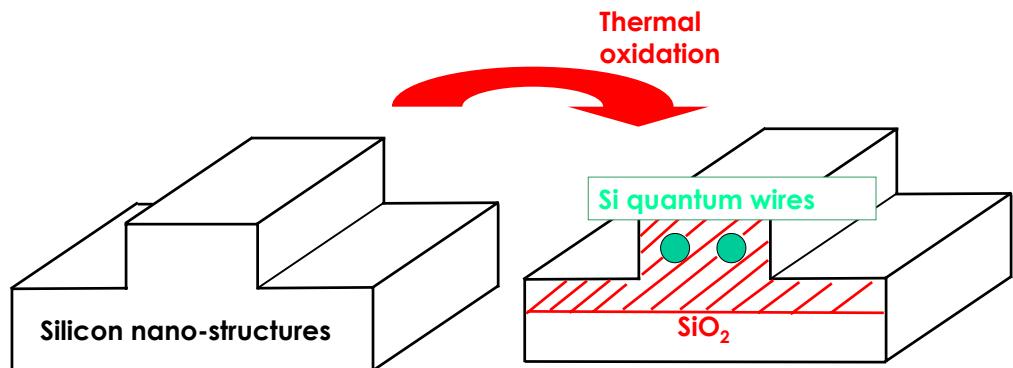
- I. MBE growth of ^{28}Si
- II. Thermal oxidation
- III. Depth profile by secondary ion mass spectrometry (SIMS)



SIMS measurements



Oxidation for nano-scale fabrication



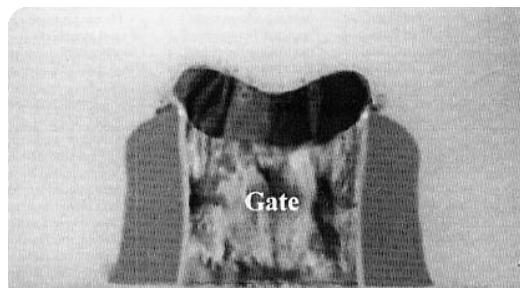
Impurity and Si diffusion

MOSFET

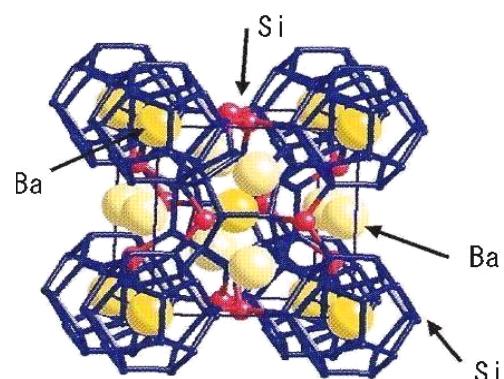
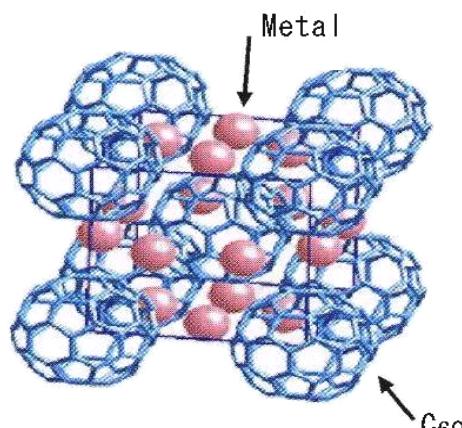
Impurity and
Si diffusion

^{28}Si layer

^{30}Si layer

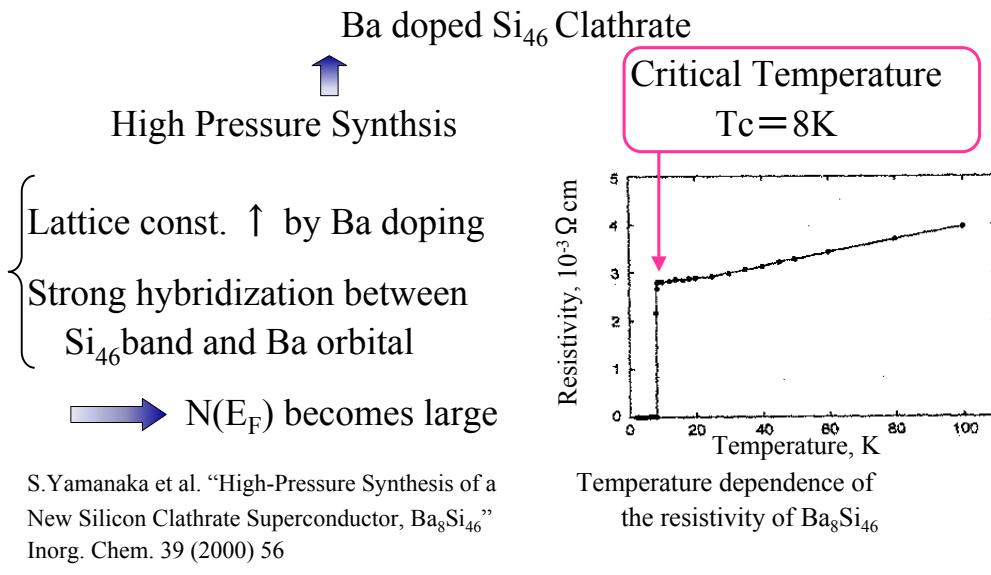


3. Superconductivity in $\text{Ba}_8\text{Si}_{46}$ clathrate



Structure of Group IV Clusters

Superconductor $\text{Ba}_8\text{Si}_{46}$



BCS model

$$T_c = 1.14 \frac{\hbar\omega}{k_B} \exp\left(-\frac{1}{N(E_F)V}\right) \propto \omega$$

$$\omega = \sqrt{\frac{k}{m}}$$

Density of states
at the Fermi Level
High (55states/eV)

e-phonon
Interaction
?

Phonon
frequency

\rightarrow check for the isotope effect (^{28}Si and ^{30}Si)

Isotope effect on T_C

From BCS Theory

$$T_c(^{30}\text{Si}) / T_c(^{28}\text{Si})$$

$$= \sqrt{28} / \sqrt{30}$$

$$= 0.97$$

From Experimental Result

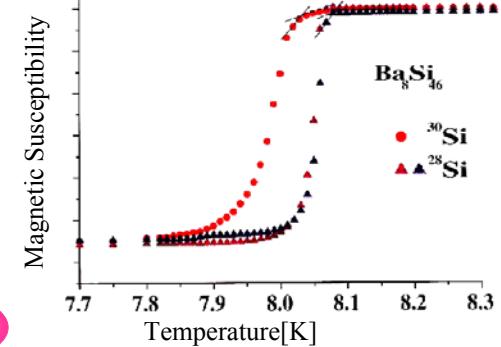
$$T_c(\text{Ba}_8^{30}\text{Si}_{46}) / T_c(\text{Ba}_8^{28}\text{Si}_{46})$$

$$= 8.02\text{K} / 8.07\text{K}$$

BCS-like

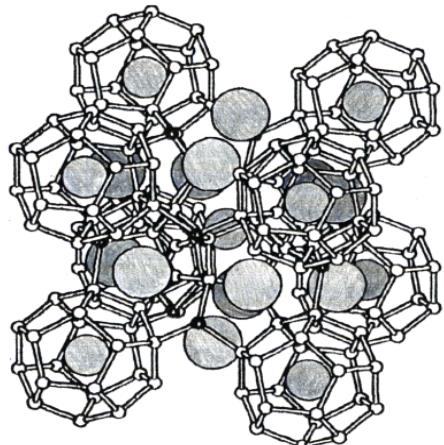
$$= 0.99$$

Osaka city university, Tanigaki group



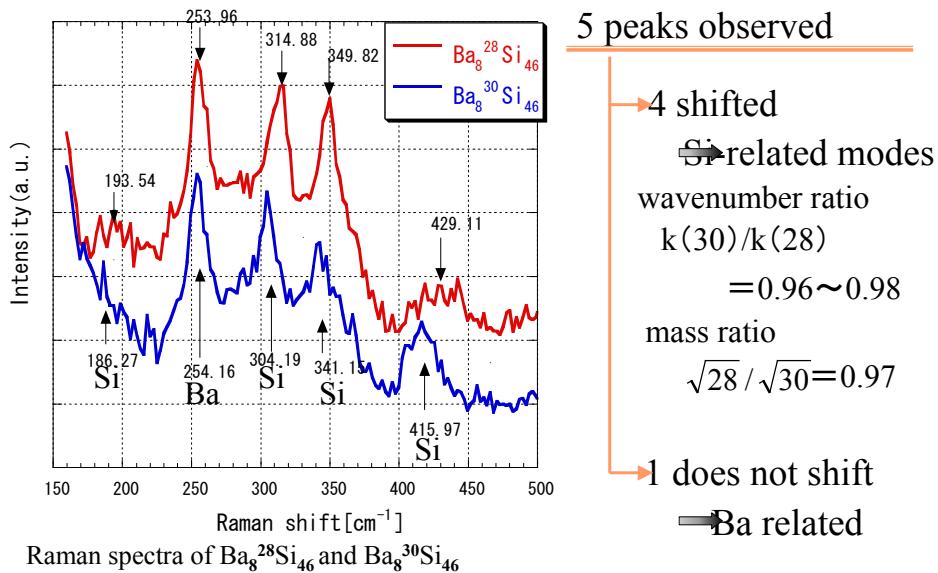
Temperature dependence of Magnetic Susceptibility of $\text{Ba}_8^{28}\text{Si}_{46}$ and $\text{Ba}_8^{30}\text{Si}_{46}$

Raman studies of vibrational modes

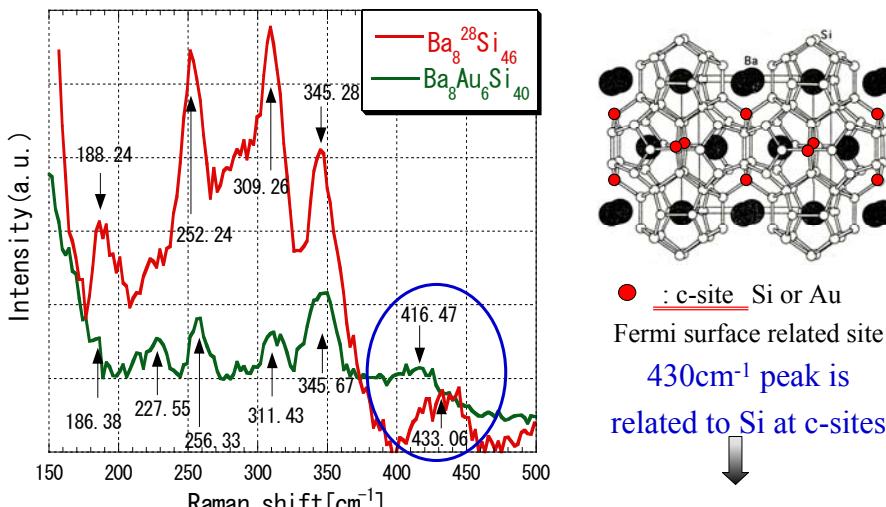


$\text{Ba}_8\text{Si}_{46}$ { Si-Si
 Si-Ba
 Ba-Ba

Raman results



Raman results



Quantum computation with spins

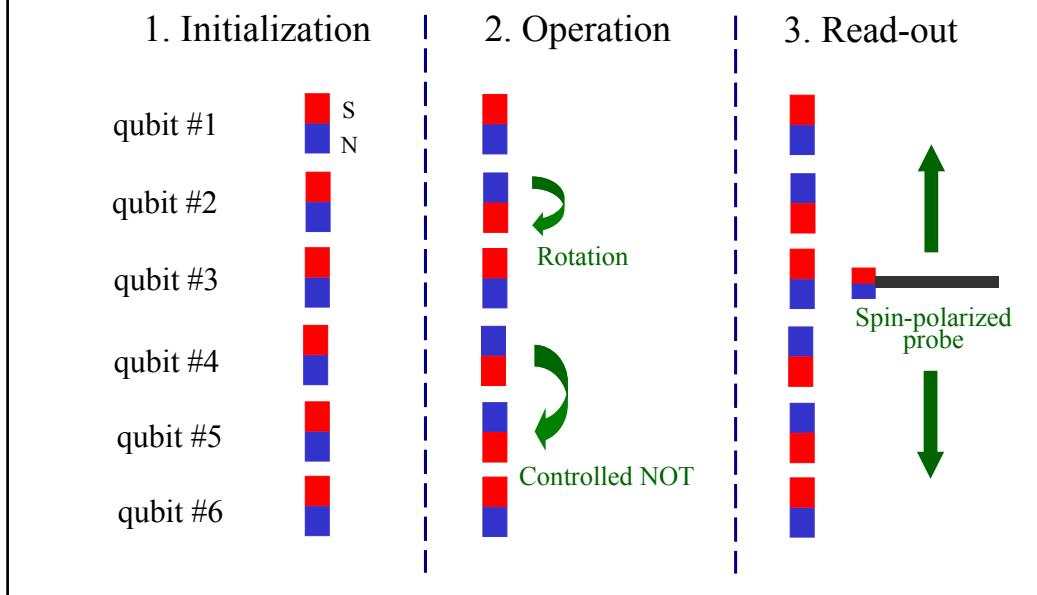
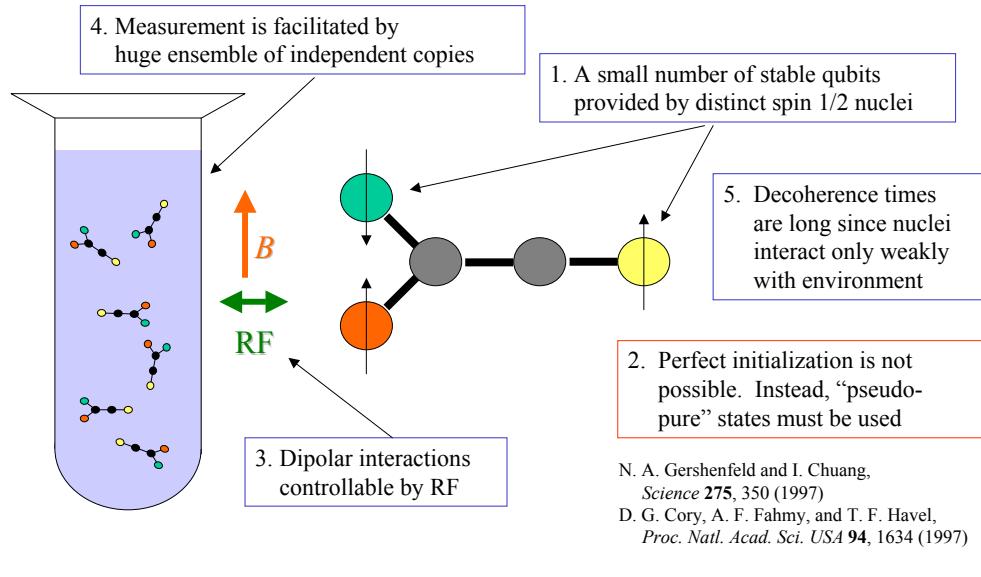


Figure of merits for QC

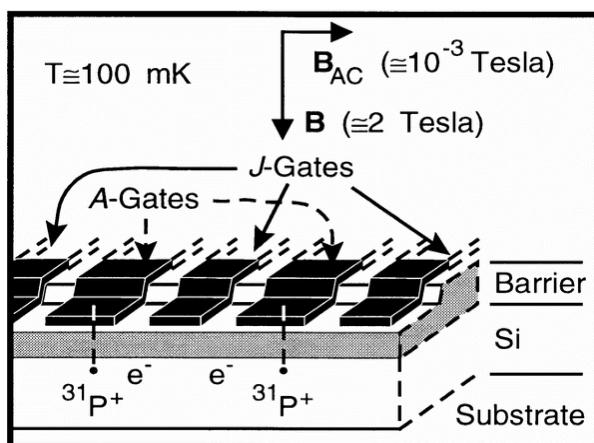
1. Number of qubits: n
available number of states 2^n

2. Maximum total computable steps: N_{\max}
$$N_{\max} = \frac{\text{phase decoherence time: } T_2}{\text{time needed for each operation: } t_s}$$

Solution NMR Quantum Computation



Solid-State Impurity NMR QC



1. Isolated impurity nuclei provide qubits
2. Low temperature electrons allow initialization
3. Electron-mediated interactions controlled by gates
4. Single-spin measurement via nuclear-electron coupling is proposed
5. Well-separated impurities have long decoherence times

B. E. Kane, *Nature* **393**, 133 (1998)

Motivation

Solution NMR QC

N. A. Gershenfeld and I. Chuang,
Science **275**, 350 (1997)
D. G. Cory, A. F. Fahmy, and T. F. Havel,
Proc. Natl. Acad. Sci. USA **94**, 1634 (1997)

Advantages:
Ensemble measurement
Natural (chemical) fabrication

Disadvantages:
Challenging to scale to many qubits and/or gates
Initialization difficult

Solid-State Impurity QC

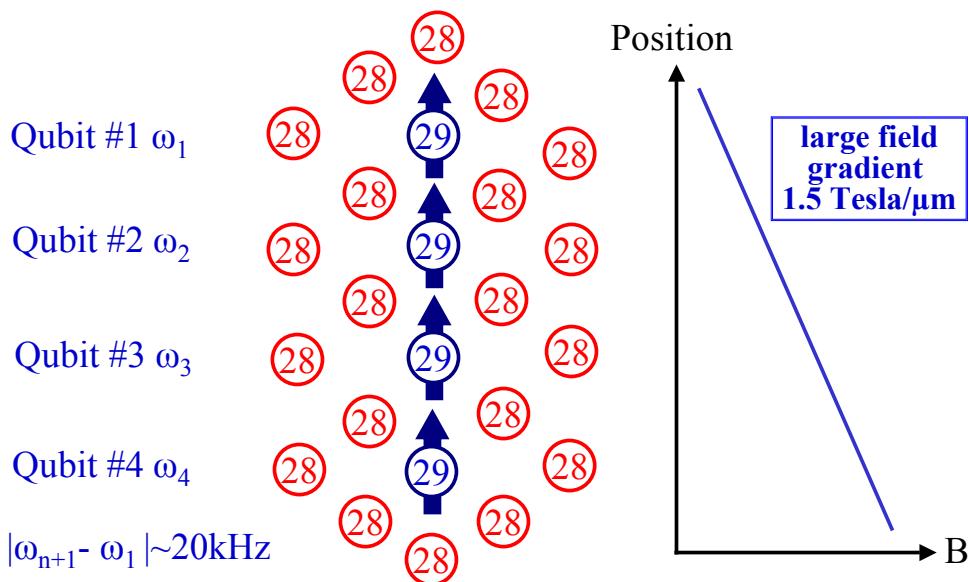
B. E. Kane, *Nature* **393**, 133 (1998)
R. Vrijen, et al., *Phys. Rev. A* **62**, 012306 (2000)
G.P. Berman, G. D. Doolen, P. C. Hammel, and
V. I. Tsifrinovich, *Phys. Rev. B* **61**, 14694 (2000).

Advantages:
Scalable!
Can cool to low temperatures for initialization

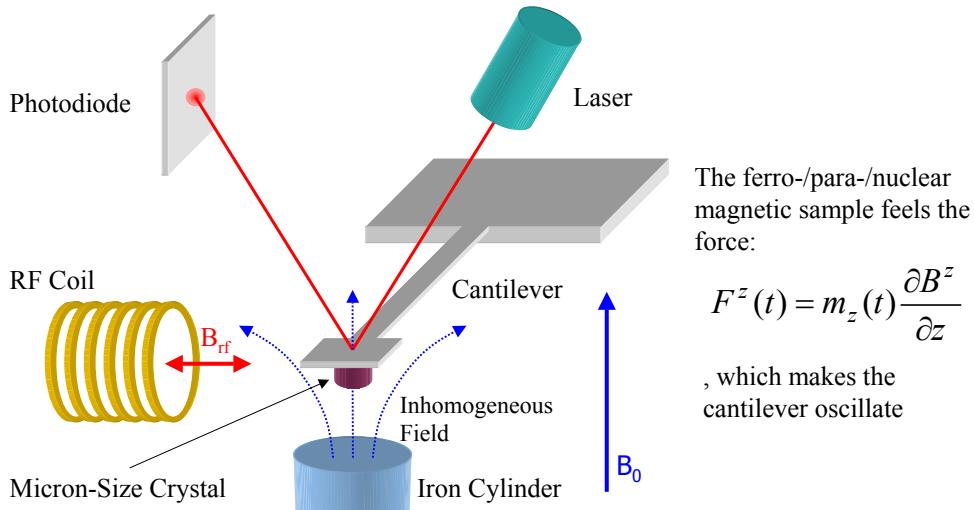
Disadvantages:
Need single-spin measurement
Challenging fabrication

All Silicon QC uses advantages of both!

^{29}Si nuclear spin quantum computer



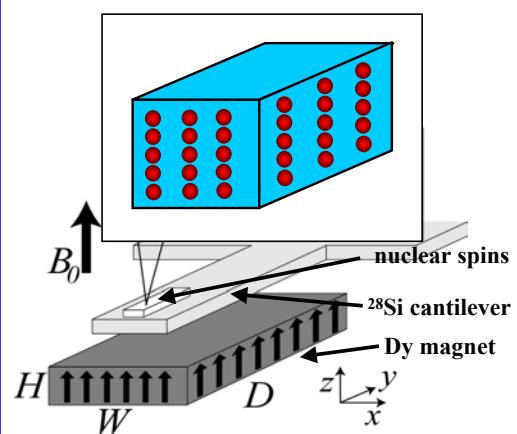
Magnetic Resonance Force Microscopy



An all silicon quantum computer

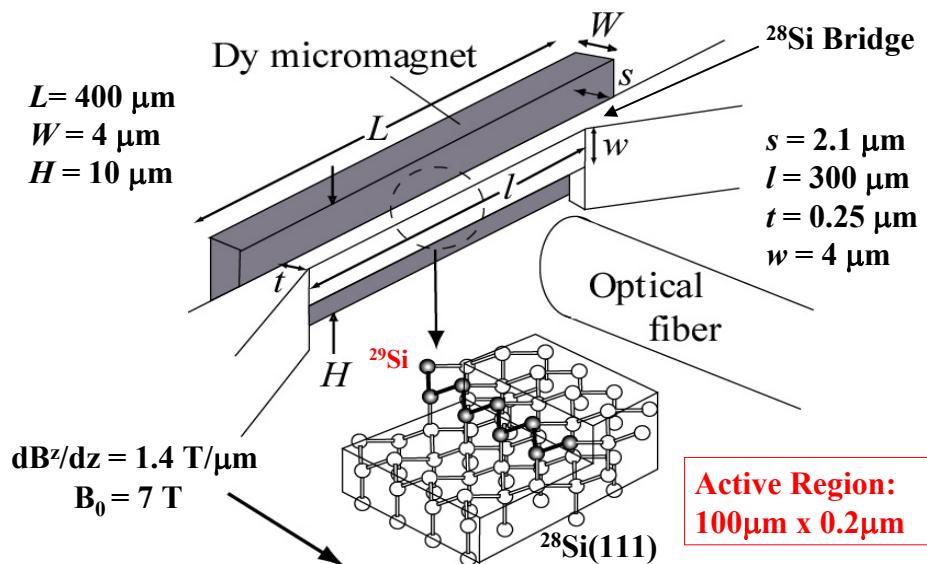
- **Qubits are spin-1/2 ^{29}Si nuclei in a ^{28}Si crystal.** They are distinguished by a one-dimensional field gradient.
- Initialization is accomplished by cooling, optical pumping, “boosting,” and “pseudo-pure state” techniques.
- Qubit interactions (decoupling and recoupling) are accomplished with RF pulse sequences.
- An ensemble of copies, orthogonal to the gradient direction, allow measurement by MRFM.
- Decoherence times are limited by pulse sequence design, crystal purity, and cantilever stability.

^{29}Si wires embedded in the ^{28}Si matrix



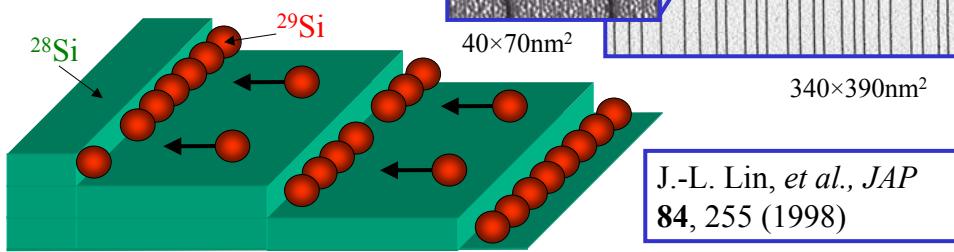
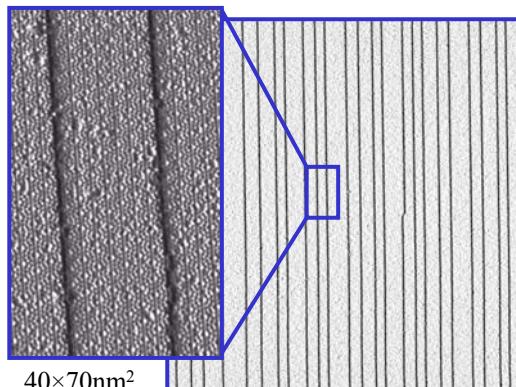
Improvement of Ladd, Goldman, Yamaguchi and Yamamoto, quant-ph/0009122 (2001)

Alternative configuration



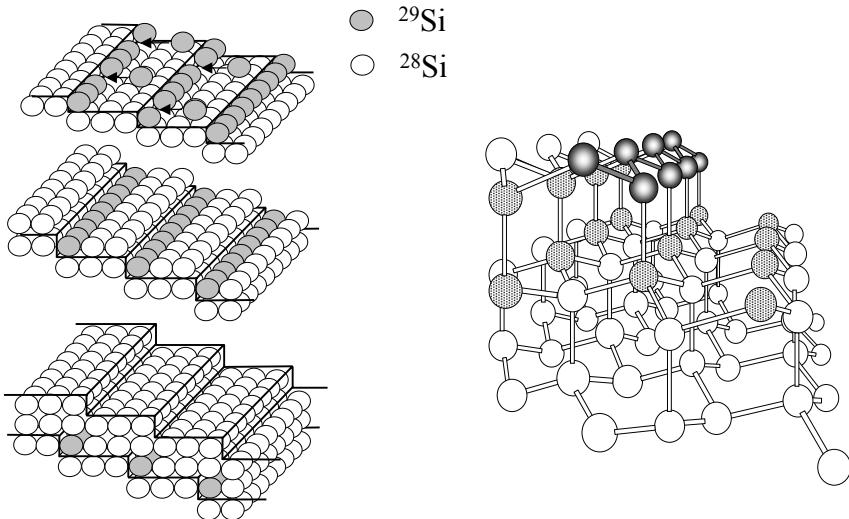
^{29}Si wire fabrication

- Form regular step arrays on slightly miscut $^{28}\text{Si}(111)7\times 7$ surface ($\sim 1^\circ$ from normal)
- Steps are *straight*, with about 1 kink in 20000 sites.
- ^{29}Si chains formed by “Step Decoration” from ^{28}Si steps
- Angle of miscut controls chain spacing

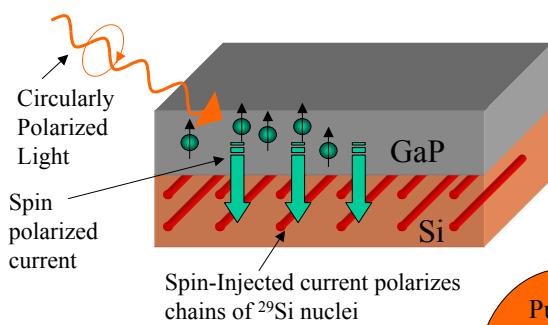


J.-L. Lin, et al., JAP
84, 255 (1998)

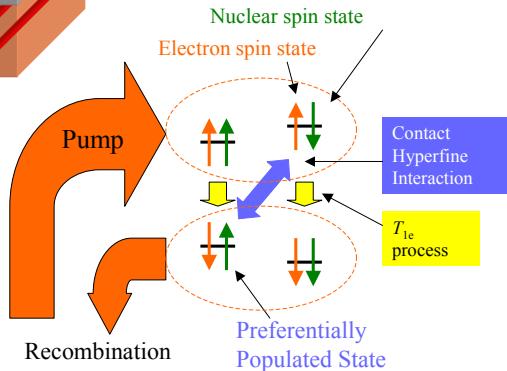
MBE fabrication of ^{29}Si wire copies



Polarization by optical pumping

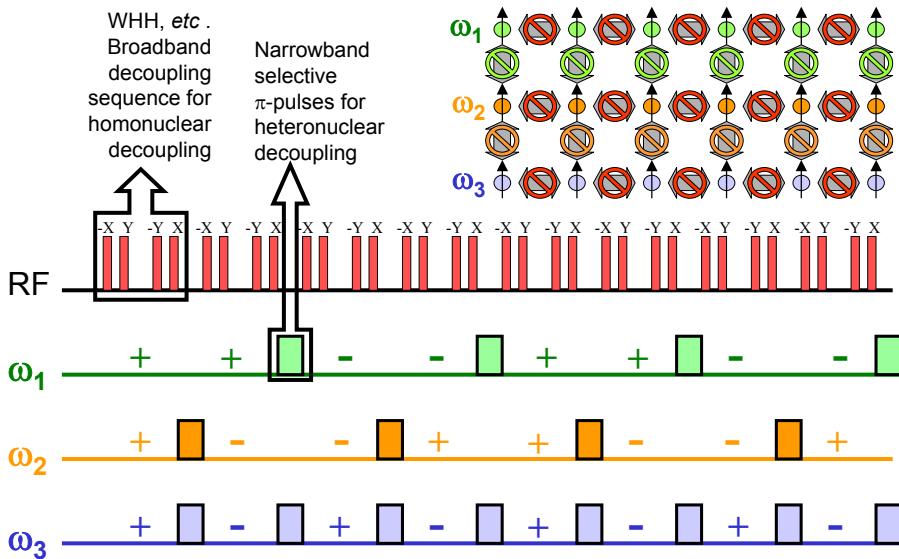


The spin-polarized conduction electrons are cleared away after polarization, removing them as decoherence source



G. Lampel, *Phys. Rev. Lett.* **20**, 491 (1967)
R. Tycko, *Solid State Nuclear Magnetic Resonance* **11**, 1 (1998)

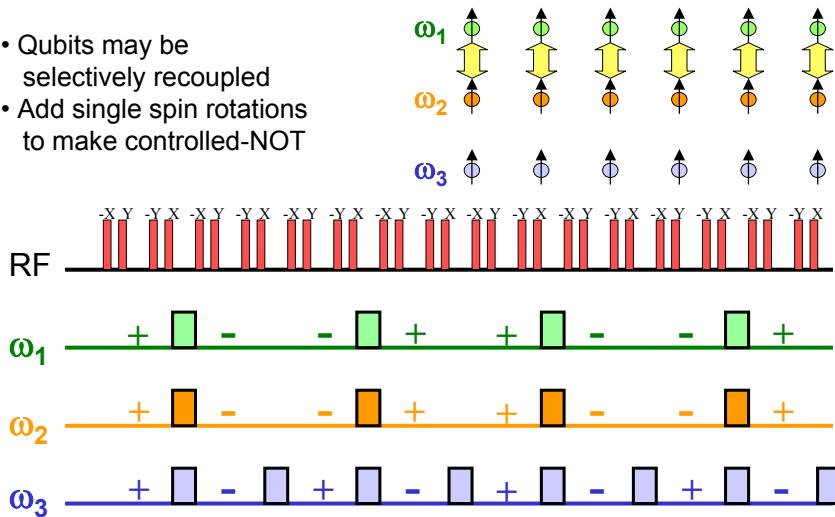
Operation (decoupling)



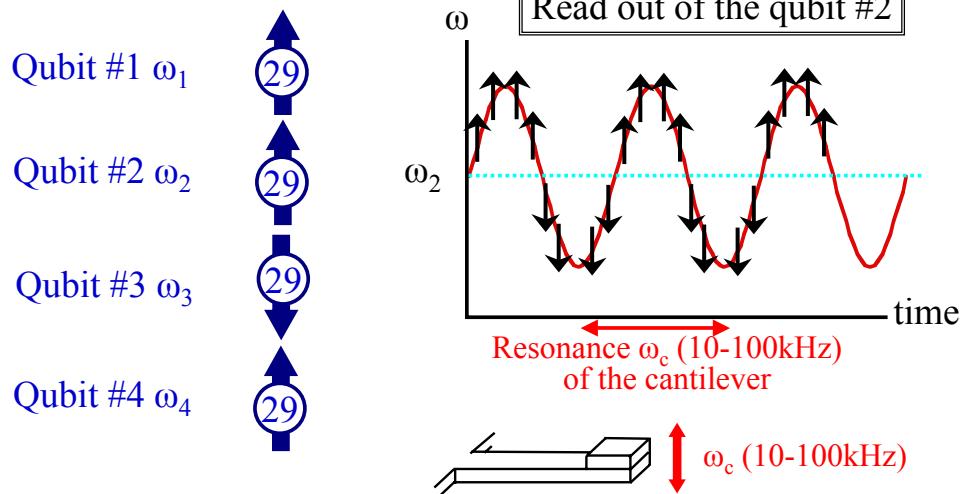
Operation (recoupling)

D. W. Leung, I. Chuang, F. Yamaguchi and Y. Yamamoto, Phys. Rev. A, 61(4) 042310/1 (1999)

- Qubits may be selectively recoupled
- Add single spin rotations to make controlled-NOT



Read-out by the MRFM cantilever



SNR and number of qubits

Force resolution for a cantilever in the thermal limit:

$$F_{\min} = \sqrt{4k k_B T B / \omega_0 Q}$$

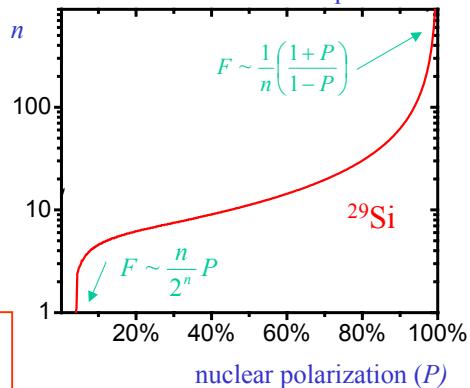
Force generated from a single atomic plane:

$$F(t) = M_z(r, t) \frac{\partial B_z}{\partial z}$$

Magnetization for nuclear spins in plane:

$$M_z = \gamma \hbar I N \left[\left(\frac{1+P}{2} \right)^n - \left(\frac{1-P}{2} \right)^n \right]$$

Number of qubits (n) for SNR = 1 vs. nuclear polarization



N = number of qubit copies
 n = number of qubits in QC

Decoherence and the maximum operation step

$$\frac{1}{T_2} = \frac{1}{2T_1} + \frac{\gamma^2}{2} \int_{-\infty}^{\infty} \langle \partial B_Z(t) \partial B_Z(0) \rangle dt + \left(\langle [H_{\text{dip}}^{\text{res}}, [H_{\text{dip}}^{\text{res}}, I^X]] \rangle / \langle I^X \rangle \right)^{1/2}$$

DC spectral density of local fluctuating field Second Moment due to residual dipolar couplings

Primary Decoherence Sources:

Residual Dipolar Couplings

Reversible in principle
Present sequence: $T_2 \sim 10$ ms

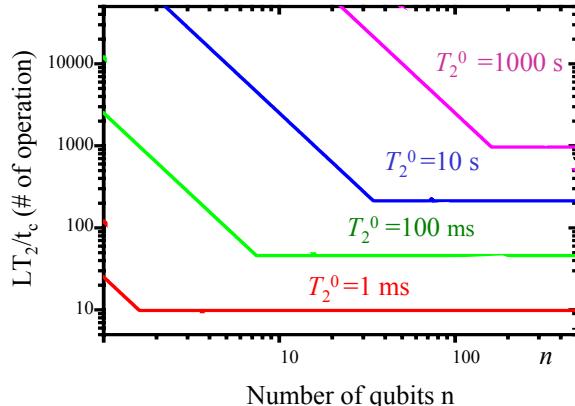
Cantilever Drift

Thermal equilibrium: $T_2 \sim 200$ ms
Feedback control $\Rightarrow T_2 \sim 1$ hour

Paramagnetic Impurities

Assuming very dilute impurities,
 $T_2 \sim (\omega_0 T_{1e})^{-1/2} T_1 \sim 1$ minute,
but much shorter for
nuclei near impurity

Clock period $t_c = L n^2 / \Delta \omega$ set by pulse sequence.
 \Rightarrow Number of logic gates T_2 / t_c is limited

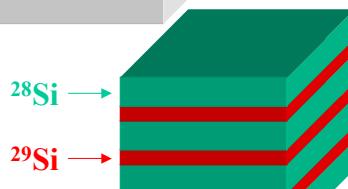


Step by step



Step.1 for Cantilever Fabrication & MRFM Readout

Few-hundred-nanometer-thick ^{29}Si on natural Si substrate



Step.2 toward Quantum Computation

$(^{29}\text{Si})_n / (^{28}\text{Si})_m$ isotope silicon superlattices with various n & m



Step.3 for First Logic Gates

Two single-layer of ^{29}Si as qubits

Our estimate allows a few logic gates in particular configurations, which are barely enough for “*proof of principle*”

Why ^{29}Si in ^{28}Si

- Established crystal growth, processing and isotope engineering technologies
- Longest possible decoherence time
No extrinsic electron and nuclear spins, reduced magnetic impurities
- Minimum cross-talk between qubit copies but enough ensemble of qubit copies
- ^{28}Si matrix provides natural means for optical pumping and detection of ^{29}Si nuclear spins
- Highest-possible-Q magnetic resonance force microscope (MRFM) cantilever
- Possible integration with Si CMOS and SET circuits